

Electronic Supplementary Information for:

Structural Controls of AuNR@mSiO₂: Tuning of the SPR, and Manipulations of the Silica Shell Thickness and Structure

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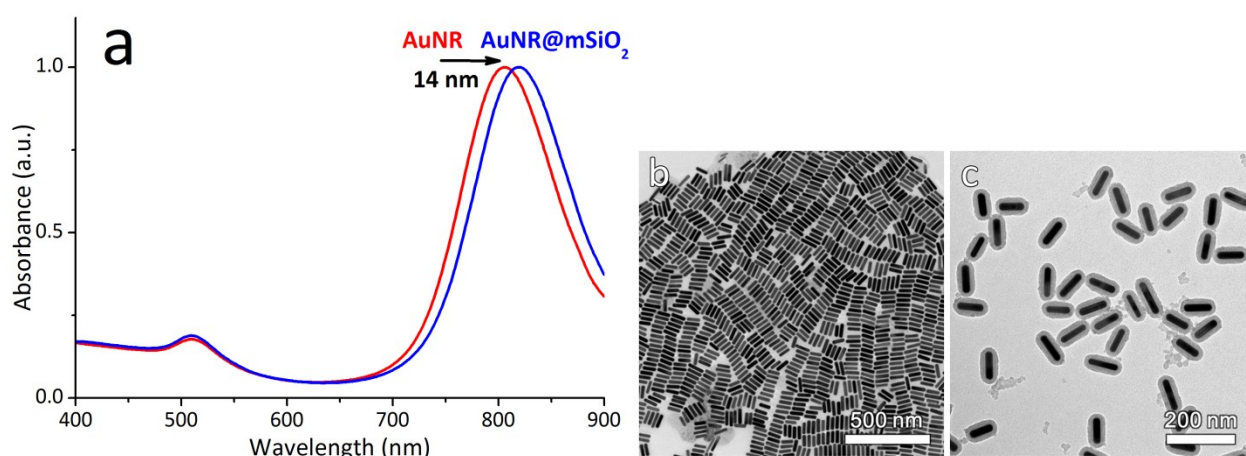


Fig. S1 (a) Normalized UV-vis spectra of the prepared AuNRs and AuNR@mSiO₂. (b, c) TEM images of the corresponding AuNRs and AuNR@mSiO₂.

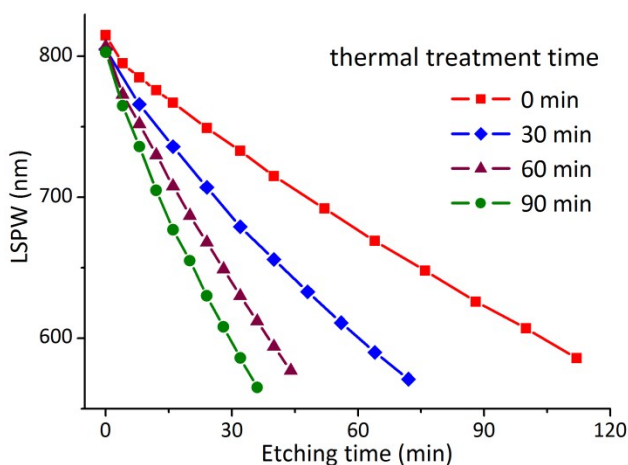


Fig. S2 Influences of different time of thermal treatment in ethanol-water solution on etching-caused LSPW changes of AuNR@mSiO₂.

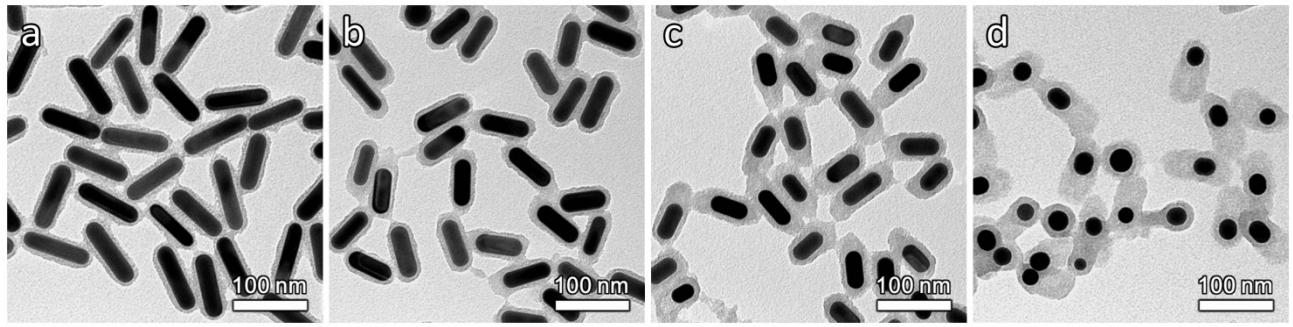


Fig. S3 TEM images of AuNR@mSiO₂ in ethanol-water solution with the different etching time. The etching time and silica shell thicknesses at side of AuNRs were: (a) 0 min, 8.1 ± 0.9 nm, (b) 24 min, 8.0 ± 0.6 nm, (c) 56 min, 8.6 ± 0.9 nm, and (d) 96 min, 9.8 ± 1.1 nm, respectively.